

Substitute for form 1449A/PTO	ATTORNEY'S DKT No. 001425-117	APPLICATION No. 10/043,190
INFORMATION DISCLOSURE STATEMENT BY APPLICANT	APPLICANT Hiroshi NOGAMI	
	FILING DATE January 14, 2002	GROUP 1744

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FOREIGN PATENT DOCUMENTS						
Examiner Initials	Foreign Patent Document		Country	Date of Publication (MM-DD-YYYY)	Translation	
	Number	Kind Code (if known)			Yes	No
MK	7-201749		Japan	08-04-1995		
MK	2837087		Japan	10-09-1998		

NON-PATENT LITERATURE DOCUMENTS	
Examiner Initials	Include name of author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.
MK	Shingo KADOMURA et al., "ANISOTROPIC ETCHING USING DEPOSITION OF SULFUR, Sony Corporation, Semiconductor World, January 1993, pp. 1-11, and translation
MC	Ken FUJITA et al., "X-RAY PHOTOELECTRON SPECTROSCOPIC STUDIES ON PYROLYSIS OF PLASMA-POLYMERIZED FLUOROCARBON FILMS ON Si", Jpn. J. Appl. Phys. volume 34 (1995), pp. 304-306, Part 1, NO. 1, January 1995
MK	Robert C. REID et al., "THE PROPERTIES OF GASES AND LIQUIDS", McGraw-Hill, Inc., Appendix B, Index. 1987
	R. Byron BIRD et al., "TRANSPORT PHENOMENA", Jon Wiley & Sons, pp. 508-509 and 512-513
MK	Riccardo d'AGOSTINO et al., "PLASMA ETCHING OF Si and SiO ₂ in SF ₆ -O ₂ MIXTURES", J. Appl. Phys. 52(1), January 1981, pp. 162-167
Examiner Signature	
	Date Considered
	06/12/03

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant. SFND TO: Assistant Commissioner for Patents, Washington, D.C. 20231.

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Substitute for forms 1449A/PTO & 1449B/PTO

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ATTORNEY's DKT No.
001425-117APPLICATION NO.
10/043,190SECOND INFORMATION DISCLOSURE
STATEMENT BY APPLICANTAPPLICANT
Hiroshi Nogami
FILING DATE
January 14, 2002GROUP
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U.S. PATENT DOCUMENTS

Examiner Initials	Document Number	Kind Code (if known)	Name of Patentee or Applicant of Cited Document	Issue/Publication Date (MM-DD-YYYY)
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	5,449,410		Chang et al.	09-12-1995
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<i>MK</i>	6-260434		Japan	09-16-1994	Abst.
<i>MK</i>	5-21393		Japan	01-29-1993	Abst.

NON PATENT LITERATURE DOCUMENTS

Examiner Initials	Include name of author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.
<i>MK</i>	Robert C. REID et al. "Lennard-Jones Potentials as Determined from Viscosity Data (Appendix B)", <i>The Properties of Gases and Liquids</i> , McGraw-Hill, Inc., Copyright 1987, p.734, Index
	R. Byron BIRD et al. "Diffusivity and the Mechanisms of Mass Transport; Theory of Ordinary Diffusion in Gases at Low Density", <i>Transport Phenomena</i> , John Wiley & Sons, Inc., Copyright 1960, p. 508-513
	A new technique for diagnostics of a radio-frequency parallel-plate remote plasma; N. Sano et al.; <i>Appl. Phys. Lett</i> 65 (2), 11 July 1994 pages 162-164.
	Infrared spectroscopic study of SiO _x films produced by plasma enhanced chemical vapor deposition; J. Vac.Sci. Technol. A4(3), May/June 1986; pages 689-694.
	Improvement of structural and electrical properties in low-temperature gate oxides for poly-Si TFTs by controlling O ₂ /SiH ₄ ratios; AM-LCD 1997; pages 87-90.
<i>MK</i>	"Flow of Atoms and Molecules—Rarefied Gas Dynamics and its Applications", section 2.6.4, The Japan Society of Mechanical Engineers, 1996, Kyoritsu Shuppan Co., Ltd.

Examiner Signature	<i>mk</i>	Date Considered	06/12/03
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